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(54) Title: EXTREME ULTRAVIOLET MASK BLANK WITH MULTILAYER ABSORBER AND METHOD OF MANUFACTURE

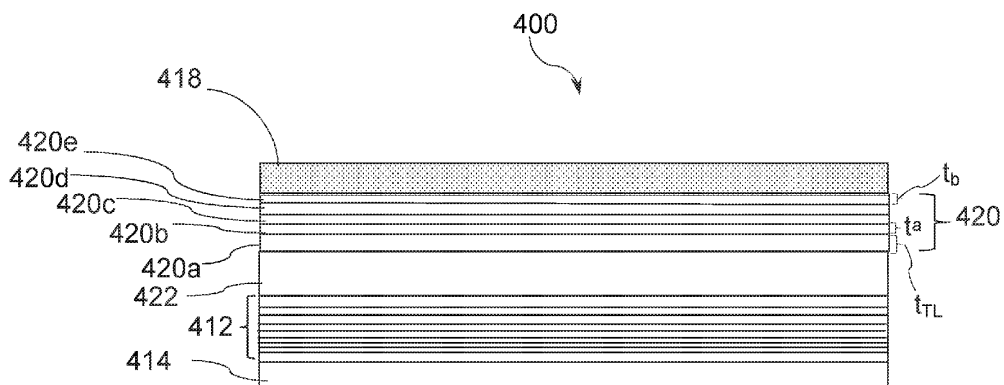


FIG. 5

(57) Abstract: Extreme ultraviolet (EUV) mask blanks, methods for their manufacture and EUV lithography systems are disclosed. The EUV mask blanks comprise an absorber including a tuning layer and a stack of absorber layers of a first material A and a second material B.



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